

09/891, 905

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 6,767,787 B2
DATED : July 27, 2004
INVENTOR(S) : Koh et al.

Page 1 of 1

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 6,

Line 10, should read -- A method of forming a plurality of channel regions between isolation --

Lines 26 and 27, should read -- using the mask as an implant mask, thereby forming an implant region in only the first and second portions to --

Line 29, should read -- forming a plurality of gate electrodes on the implant --

Lines 34-37, should read -- from the implant region, wherein the separate channel regions are self-aligned to the plurality of gate electrodes. --

Line 62, should read -- 8. A method of forming a plurality of channel regions between isolation --

Column 7,

Line 11, should read -- single implant region in only the first and second --

Line 14, should read -- implant region; and --

Lines 19-21, should read -- and second spaced apart channel regions from the single implant region. --

Column 8,

Line 1, should read -- A method of forming a plurality of channel regions between --

Lines 13-14, should read -- using the mask as an implant mask, thereby forming an implant region in the exposed portion of the substrate --

Line 16, should read -- forming a plurality of gate electrodes on the implant --

Lines 22-26, should read -- separate channel regions from the implant region, wherein the separate channel regions are self-aligned to the plurality of gate electrodes. --

Signed and Sealed this

First Day of February, 2005



JON W. DUDAS
Director of the United States Patent and Trademark Office